

L Number	Hits	Search Text	DB	Time stamp
1	1	("6294805").PN.	USPAT; US-PGPUB	2004/10/27 09:01
2	203945	SiN or Si ₃ N ₄ or siliconnitride or nitride or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4" or "silicon N" or "silicon-N" or "siliconN" or "Si nitride" or "Si-nitride" or "Sinitride"	USPAT; US-PGPUB	2004/10/27 09:04
3	0	((("6294805").PN.) and (SiN or Si ₃ N ₄ or siliconnitride or nitride or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4" or "silicon N" or "silicon-N" or "siliconN" or "Si nitride" or "Si-nitride" or "Sinitride"))	USPAT; US-PGPUB	2004/10/27 09:08
4	157996	CMP or polish\$	USPAT; US-PGPUB	2004/10/27 09:08
5	0	((("6294805").PN.) and (CMP or polish\$))	USPAT; US-PGPUB	2004/10/27 09:46
6	1580541	phosphoric or phosphorous or P	USPAT; US-PGPUB	2004/10/27 09:47
7	1	((("6294805").PN.) and (phosphoric or phosphorous or P))	USPAT; US-PGPUB	2004/10/27 09:47
8	48	((siliconnitride or "silicon nitride" or SiN or Si ₃ N ₄ or "silicon-nitride" or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4" or "Si nitride" or "Si-nitride" or "Sinitride" or "silicon N" or "silicon-N" or "siliconN") with (TiN or titaniumnitride or "Ti nitride" or "Ti-nitride" or "Tinitride" or "titanium N" or "titanium-N" or "titaniumN")) with (("hard mask" or "hard-mask" or (hard) with (mask)))	USPAT; US-PGPUB	2004/10/27 10:01
9	10	((siliconnitride or "silicon nitride" or SiN or Si ₃ N ₄ or "silicon-nitride" or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4" or "Si nitride" or "Si-nitride" or "Sinitride" or "silicon N" or "silicon-N" or "siliconN" or TiN or titaniumnitride or "Ti nitride" or "Ti-nitride" or "Tinitride" or "titanium N" or "titanium-N" or "titaniumN") with (TiO or TiO ₂ or titaniumoxide or "titanium oxide" or "titanium-oxide" or "Ti oxide" or "Ti-oxide" or "Tioxide" or "titanium O" or "titanium-O" or "titaniumO")) with (("hard mask" or "hard-mask" or (hard) with (mask)))	USPAT; US-PGPUB	2004/10/27 10:09
10	3796583	@ad<20020904	USPAT; US-PGPUB	2004/10/27 10:09

11	7	(((siliconnitride or "silicon nitride" or SiN or Si ₃ N ₄ or "silicon-nitride" or "Si.sub.3N.sub.4" or "Si.sub.3N.sub.4" or "Si nitride" or "Si-nitride" or "Sinitride" or "silicon N" or "silicon-N" or "siliconN" or TiN or titaniumnitride or "Ti nitride" or "Ti-nitride" or "Tinitride" or "titanium N" or "titanium-N" or "titaniumN") with (TiO or TiO ₂ or titaniumoxide or "titanium oxide" or "titanium-oxide" or "Ti oxide" or "Ti-oxide" or "Tioxide" or "titanium O" or "titanium-O" or "titaniumO")) with (("hard mask" or "hard-mask" or (hard) with (mask)))) and @ad<20020904	USPAT; US-PGPUB	2004/10/27 10:16
12	280913	capacitor	USPAT; US-PGPUB	2004/10/27 10:16
13	5	(((siliconnitride or "silicon nitride" or SiN or Si ₃ N ₄ or "silicon-nitride" or "Si.sub.3N.sub.4" or "Si.sub.3N.sub.4" or "Si nitride" or "Si-nitride" or "Sinitride" or "silicon N" or "silicon-N" or "siliconN" or TiN or titaniumnitride or "Ti nitride" or "Ti-nitride" or "Tinitride" or "titanium N" or "titanium-N" or "titaniumN") with (TiO or TiO ₂ or titaniumoxide or "titanium oxide" or "titanium-oxide" or "Ti oxide" or "Ti-oxide" or "Tioxide" or "titanium O" or "titanium-O" or "titaniumO")) with (("hard mask" or "hard-mask" or (hard) with (mask)))) and @ad<20020904) and capacitor	USPAT; US-PGPUB	2004/10/27 10:16

EAST - [10633193.3.1]

☐ Drafts
☐ Pending
☒ Active
 ☒ L1: (1) ("629+805").PN.
 ☒ L2: (203945) SiN or Si₃N₄ or siliconnitride or nitride or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4..."
 ☒ L3: (0) 1 and 2
 ☒ L4: (157996) CMP or polish\$
 ☒ L5: (0) 1 and +
 ☒ L6: (1580541) phosphoric or phosphorous or P
 ☒ L7: (1) 1 and 6
 ☒ L8: (+8) ((siliconnitride or "silicon nitride" or SiN or Si₃N₄ or "silicon-nitride" or "Si.sub.3...
 ☒ L9: (10) ((siliconnitride or "silicon nitride" or SiN or Si₃N₄ or "silicon-nitride" or "Si.sub.3...
 ☒ L10: (3796583) @ad<20020904
 ☒ L11: (7) 9 and 10
 ☒ L12: (280913) capacitor
 ☒ L13: (5) 11 and 12
☐ Failed
☐ Saved
☐ Favorites
☐ Tagged (0)
☐ UDC

Default operator: ☒ Highlight all hit terms initially

11 and 12

	U	Document	Issue Da	Page	Title	Current	Current X	Retrieval	Inventor	SCP	23
1	<input type="checkbox"/>	US 200301	2003091	7	Plasma etching of Ir and PZ	438/710	257/E21.0		Ying Chentsau et al.	<input type="checkbox"/>	<input type="checkbox"/>
2	<input type="checkbox"/>	US 200100	20011120	11	METHOD OF PLASMA	438/710	257/E21.0		ATHAVALE S	<input type="checkbox"/>	<input type="checkbox"/>

Ready

NUM